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Supporting information for

Analysis and suppression of scattering interference for arsenic using a dispersive atomic fluorescence spectrometry based on ultraviolet digital micromirror device spectrometer

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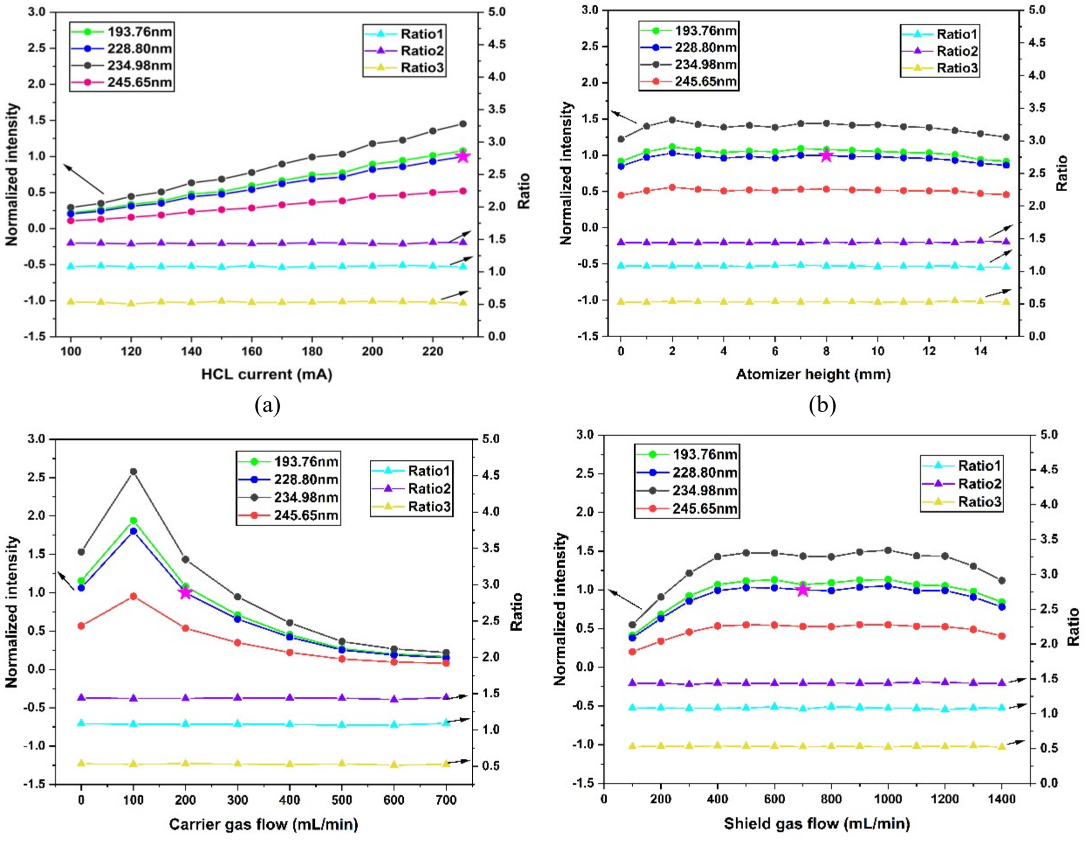
1. The influence of instrument parameters on ISI



(a) (b)

(c) (d)

Fig. S-1 Influence of instrument parameters on ISI (a) HCL current; (b) atomizer height; (c) carrier gas flow; (d) shield gas flow.